

Atmospheric Pressure Plasma Technologies and Applications

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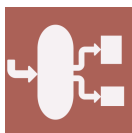
Message from the Guest Editors

In recent years, a large variety of plasma sources operating at atmospheric pressure have been developed. Plasma technology is gaining great attention as a “green” alternative, reducing the use of chemicals in many processes such as nanomaterials synthesis, surface treatment, disinfection, wound healing, and seeds decontamination. Since plasma is a complex system of charged particles (electrons and ions), chemically highly reactive radicals, excited atoms, and electromagnetic radiation including UV, the synergetic action of all these components makes plasma-based processes highly efficient and “clean” at the same time.

This Special Issue focuses on recent advances in atmospheric pressure plasma technologies and applications. You are invited to submit cutting-edge research, theoretical and experimental studies, as well as comprehensive reviews in this field:

- atmospheric pressure plasma
- plasma technology
- plasma applications
- cold atmospheric pressure plasma
- bio-medical plasma applications
- plasma in agriculture
- plasma technology in nanomaterials
- plasmas with liquids





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Message from the Editor-in-Chief

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